

09/972,428

SHEET 11 of 12

<b>INFORMATION DISCLOSURE CITATION</b>  <b>PTO-1449</b>		<b>Atty. Docket No.</b> NMTI 1002-4	<b>Serial No.</b> 09/972,428-3974
		<b>Applicant</b> PIERRAT, Christophe	<b>Group</b> <u>2824</u> <del>Not Yet Assigned</del>
<b>Filing Date</b> 10/5/2001			
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>			
<b>EXAMINER'S INITIALS</b>	<b>CITATION</b>		
JSR	Morimoto, H., et al., "Next Generation Mask Strategy - Technologies are Ready for Mass Production of 256MDRAM?", SPIE, Vol. 3236, pp. 188-189 (1997).		
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	Kuo, C., et al., "Extension of Deep-Ultraviolet Lithography for Patterning Logic Gates Using Alternating Phase Shifting Masks", J. Vac. Sci. Technol. B, Vol. 17, No. 6, pp. 3296-3300, November/December 1999.		
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EXAMINER:

*J. Ruggles*

Date Considered:

*5/8/03*

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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